



Subject card

Subject name and code	Semiconductor thin-film nanostructures, PG_00071210						
Field of study	Nanotechnology						
Date of commencement of studies	February 2027		Academic year of realisation of subject			2026/2027	
Education level	second-cycle studies		Subject group			Specialty subject group Subject group related to scientific research in the field of study	
Mode of study	Full-time studies		Mode of delivery			at the university	
Year of study	1		Language of instruction			Polish	
Semester of study	1		ECTS credits			1.0	
Learning profile	general academic profile		Assessment form			assessment	
Conducting unit	Institute of Nanotechnology and Materials Engineering -> Faculty of Applied Physics and Mathematics -> Faculties of Gdańsk University of Technology						
Name and surname of lecturer (lecturers)	Subject supervisor		prof. dr hab. inż. Wojciech Sadowski				
	Teachers						
Lesson types	Lesson type	Lecture	Tutorial	Laboratory	Project	Seminar	SUM
	Number of study hours	15.0	0.0	0.0	0.0	0.0	15
	E-learning hours included: 0.0						
Learning activity and number of study hours	Learning activity	Participation in didactic classes included in study plan	Participation in consultation hours	Self-study	SUM		
	Number of study hours	15	1.0	9.0	25		
Subject objectives	The aim of the course is to analyze methods of fabricating semiconductor thin films and superlattices to create functional nanomaterials and quantum structures.						
Learning outcomes	Course outcome	Subject outcome	Method of verification				
	[K7_W02] has in-depth, theoretically grounded and detailed knowledge of phenomena, methods, and theories related to nanotechnology, as well as of related and allied fields of science or engineering	The student has in-depth, theoretically based knowledge of methods for producing structurally ordered thin-film materials and quantum nanostructures for various applications.	[SW1] Assessment of factual knowledge				
	[K7_U01] is able to formulate hypotheses, plan and conduct experimental research, critically analyze results, verify hypotheses, draw conclusions, and formulate well-founded opinions within nanotechnology and related physical and natural sciences. Recognizes economic and non-technical aspects of the activities performed	The student is able to learn independently, obtain information from literature and other appropriately selected sources in Polish and English in the aspect of manufacturing nano-sized materials and nanostructures.	[SU3] Assessment of ability to use knowledge gained from the subject				

Subject contents	<p>Course content – lecture Heterogeneous nucleation of a new 2D phase - thermodynamics and kinetics of the process.</p> <p>Lattice matching in the crystallization of thin semiconductor films.</p> <p>Vapor phase epitaxy (VPE) and its modifications (MOVPE).</p> <p>Liquid phase epitaxy (LPE), process thermodynamics.</p> <p>Molecular beam epitaxy (MBE), ballistic jet.</p> <p>Non-epitaxial thin film deposition methods (ALD, magnetron deposition).</p> <p>Examples of the fabrication and quantum properties of thin film and nano-sized structures.</p>								
Prerequisites and co-requisites	A course on the basics of physics, chemistry, thermodynamics and an introduction to nanotechnology.								
Assessment methods and criteria	<table border="1"> <thead> <tr> <th data-bbox="456 734 790 763">Subject passing criteria</th> <th data-bbox="802 734 1141 763">Passing threshold</th> <th data-bbox="1145 734 1469 763">Percentage of the final grade</th> </tr> </thead> <tbody> <tr> <td data-bbox="456 770 790 808">Written examination covering lecture content.</td> <td data-bbox="802 770 1141 808">51.0%</td> <td data-bbox="1145 770 1469 808">100.0%</td> </tr> </tbody> </table>	Subject passing criteria	Passing threshold	Percentage of the final grade	Written examination covering lecture content.	51.0%	100.0%		
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Recommended reading	<p>Basic literature</p>	<p>Handbook of Thin-Film Technology. Edited by Hartmut Frey Hamid R. Khan. Springer-Verlag Berlin Heidelberg 2015.</p> <p>Handbook of Thin Film Deposition: Theory, Technology and Semiconductor Applications. Edited by: Dominic Schepis and Krishna Seshan. 2024 Elsevier</p> <p>2022 Roadmap for Materials for Quantum Technologies. https://arxiv.org/pdf/2202.07309</p>							
	<p>Supplementary literature</p>	<p>Molecular Beam Epitaxy: Principals, Advantages and Challenges. Mehdi Afshari. Published: 26 June 2025</p> <p>DOI: 10.5772/intechopen.1011123</p> <p>A review of molecularbeam epitaxy of wide bandgap complex oxide semiconductors. William Nunn et al. J.of Materials Research, 2021</p> <p>New Materials, New Functionalities: Molecular Beam Epitaxy of Ultra-High Conductivity Oxides. Gaurab Rimal et al. arXiv:2508.10885v1 [cond-mat.mtrl-sci] 14 Aug 2025; https://arxiv.org/html/2508.10885v1</p> <p>Quantum Technologies for Engineering: the materials challenge. Kuan Eng Johnson Goh et al.. Mater. Quantum Technol. 2 (2022) 013002. https://inspirehep.net/files/b07c029658f1fa94e6a494ad3724311d</p> <p>2022 Roadmap for Materials for Quantum Technologies. https://arxiv.org/pdf/2202.07309</p>							
	eResources addresses								

<p>Example issues/ example questions/ tasks being completed</p>	<p>Description of the heterogeneous nucleation process.</p> <p>Vapor phase epitaxy (VPE) and its modifications (MOVPE).</p> <p>Liquid phase epitaxy (LPE), process thermodynamics.</p> <p>Molecular beam epitaxy (MBE), ballistic jet.</p> <p>Non-epitaxial thin film deposition methods (ALD, magnetron deposition)</p>
<p>Practical activities within the subject</p>	<p>Not applicable</p>

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